

208544US-2



IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF :

TAKAHIRO HORIGUCHI ET AL

: EXAMINER: KACKAR, RAM N.

SERIAL NO: 09/855,493 :

FILED: MAY 16, 2001

: GROUP ART UNIT: 1763

FOR: SINGLE-SUBSTRATE-PROCESSING:
APPARATUS FOR SEMICONDUCTOR
PROCESS

RECEIVED
APR 22 2003
GROUP 1700

AMENDMENT UNDER 37 C.F.R. §1.114(c)

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

SIR:

In response to the Office Action dated December 17, 2002, please amend the above-identified patent application as follows:

IN THE CLAIMS

Please amend the claims to read as shown below:

21. (Amended) A single-substrate-processing apparatus, comprising:

C1
an airtight process chamber including a casing and configured to process a target substrate;

a worktable configured to support the target substrate within the casing of the process chamber,

a pedestal standing upright in the process chamber and connected to the worktable to support the worktable; and